

## ABSTRACT

A stamper with a sharp uneven pattern is obtained, and high precision information media can be manufactured using this stamper.

A photoresist master 100 is manufactured by forming a light absorption layer 103 with a film thickness  $T$  that satisfies  $T > 180$  (nm) and a photoresist layer 104, in that order, on top of a substrate 102, and then forming an uneven pattern 106 in the photoresist layer 104 by forming and developing a latent image, and a stamper 120 is manufactured by forming a Ni thin film 108 on top of the uneven pattern 106 of the photoresist master 100 by electroless plating, forming a Ni film 110 on top of this Ni thin film 108 by electroforming, and then separating the Ni thin film 108 and the Ni film 110 from the photoresist master 100.